

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s): Waleh et al.	
Serial No.:	
Filed: 2/24/2004	Group Art Unit:
Title: Method of Removing Organic Materials from Substrates	Examiner:
Attorney Docket No.: 95013A1a	

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Dear Sir:

This Information Disclosure Statement is submitted:

- ☒ under 37 CFR 1.97(b), or
(Within three months of filing national application; or date of entry of international application; or before mailing date of first office action on the merits; whichever occurs last)
- ☐ under 37 CFR 1.97(c) together with either a:
☐ Statement under 37 CFR 1.97(e), or
☐ a \$180.00 fee under 37 CFR 1.17(p), or
(After the CFR 1.97(b) time period, but before final action or notice of allowance, whichever occurs first)
- ☐ under 37 CFR 1.97(d) together with a:
☐ Statement under 37 CFR 1.97(e), and
☐ a \$180.00 fee set forth in 37 CFR 1.17(p).
(Filed after final action or notice of allowance, whichever occurs first, but before payment of the issue fee)

☒ Applicant(s) submit herewith Form PTO 1449-Information Disclosure Citation together with copies, of patents, publications or other information of which applicant(s) are aware, which applicant(s) believe(s) may be material to the examination of this application and for which there may be a duty to disclose in accordance with 37 CFR 1.56.

The relevance of the attached references is that this is the closest art of which Applicant is aware.

Applicant submits that the above references taken alone or in combination neither anticipate nor render obvious the present invention. Consideration of the foregoing in relation to this application is respectfully requested.

It is requested that the information disclosed herein be made of record in this application.


Respectfully submitted,

I hereby certify that this correspondence is being deposited with the United States Postal Service with sufficient postage for Express mail in an envelope addressed to the Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, or the correspondence is being facsimile transmitted to the USPTO, on the date indicated below, Airbill #EV EV 381770509.

Date of Deposit: 2/24/2004

Typed Name: L.D. Raphael

Signature:



David W. Collins

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Date: February 24, 2004

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FORM PTO-1449 U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE LIST OF PRIOR ART CITED BY APPLICANT	ATTY. DOCKET NO. D-95013A1a	SERIAL NO. (Filed Herewith)
	APPLICANT Ahmad Waleh et al	
	FILING DATE (Filed Herewith)	GROUP

U.S. PATENT DOCUMENTS

EXR IN		DOC. NO.	DATE	NAME	CLASS	SUBCLASS
	AA	4,669,544	6/1/87	Nimerick	166	300
	AB	5,030,399	7/9/91	Walles et al	264	83
	AC	5,158,100	10/27/92	Tanaka et al	134	105
	AD	4,179,071	12/18/79	Kozacka	239	397.5
	AE	4,915,912	4/10/90	Walles et al	422	160
	AF	4,778,536	10/18/88	Grebinski	134	36
	AF1	5037506	8/1991	Gupta, et al	134	902
	AG	4,363,673	12/1982	Settineri, et al	134	2
	AH	4,455,175	12/1984	Settineri, et al	134	5
	AI	4,536,222	8/1985	Settineri, et al	134	5
	AJ	5,763,016	12/1998	Levinson, et al	427	510
	AK	5,952,157	9/1999	Kato, et al	430	329
	AL	5,227,001	7/13/93	Tamaki, et al	156	345

FOREIGN PATENT DOCUMENTS

		DOC. NO.	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
							YES	NO
	AN							
	AO							
	AP							

OTHER PRIOR ART (Including Author, Title, Date, Pertinent Pages, Etc.)

	AR	Stanley Wolf and Richard N. Tauber, "Silicon Processing For The VLSI Era", <i>Process Technology</i> , Vol. 1 (1986), p. 564;
	AS	"Choose The Right Process To Strip Your Photoresist", <i>Semiconductor International</i> , February 1990, pp 83-87;
	AT	"New Concerns In Dry Oxygen Ashing", <i>Semiconductor International</i> , March 1996, p. 44; and
	AU	"What's Driving Resists Dry Stripping?", <i>Semiconductor International</i> , November 1994, pp 61-64.
	AV	Christina M. Cline, "Emerging Technology; Emerging Markets", <i>Precision Cleaning</i> , October 1996, pp 11-19
	AW	Ruth DeJule, "Managing Etch and Implant Residue", <i>Semiconductor International</i> , August 1997, pp 56-63

EXAMINER	DATE CONSIDERED
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EXAMINER: Initial if references considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

PATENT APPLICATION

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FORM PTO-1449	ATTY. DOCKET NO.	D-95013A1	SERIAL NO.	(Filed Herewith)
	APPLICANT			
	Ahmad Waleh, et al.			
FILING DATE		(Filed Herewith)	GROUP	

REFERENCE DESIGNATION U.S. PATENT DOCUMENTS

EXAMINER INITIAL	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLASS
	3893869	7/1975	Mayer, et al	134	184
	5024968	6/1991	Engelsberg	134	1
	5114834	5/1992	Nachshon, y	216	48
	5531857	7/1996	Engelsberg, et al	134	1
	5643472	7/1997	Engelsberg, et al	134	1

FOREIGN PATENT DOCUMENTS

	DOCUMENT NUMBER	DATE	NAME	CLASS	SUB CLAS	TRANSLATION	
						YES	NO
	WO9507152	3/1995	Elliott et al	B08B	3/00	x	
	WO9717164	5/1997	Genut et al	B23K	26/6	x	

OTHER REFERENCES (including Author, Title, Date, Pertinent Pages, etc.)

	Hawley's Condensed Chemical Dictionary, P 28, 1993
	Egelsberg, "Laser Assisted Cleaning Proves Promising", <u>Precision Cleaning</u> , 1994
EXAMINER	DATE CONSIDERED